



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Gaillard, et al.

Serial No.: 10/789,209

Confirmation No.: 9101

Filed:

February 27, 2004

For:

Method of Decreasing the

K Value in SIOC Layer Deposited by Chemical

Vapor Deposition

MAIL STOP AMENDMENT Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Group Art Unit: 2818

Examiner:

David Nhu

CERTIFICATE OF MAILING

37 CFR 1.8

I hereby certify that this correspondence is being deposited on 3/8, 2005 with the United States Postal Service as First Class Mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-

3/8/05

Signatu

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Supplemental Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Supplemental Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

Applicants submit that all references submitted with this disclosure were first cited in a communication from a foreign patent office dated January 10, 2005, which communication is enclosed, not more than three months prior to the filing of this Supplemental Information Disclosure Statement.

If the sum of \$180.00 is due under 37 CFR § 1.17(p) pursuant to § 1.97, the Commissioner is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to the Deposit Account No. 20-0782/AMAT/2592.C9/KMT.

Respectfully submitted,

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Substitute form 1449		Application Number	10/789,209	1
1 1 2005 SUPPL	EMENTAL	Filing Date	FEBRUARY 27, 2004	
INFORMATIC	N DISCLOSURE	First Named Inventor	GAILLARD, ET AL.	•
RADES ATEMENT	BY APPLICANT	Group Art Unit	2818	
	2.7	Examiner Name	DAVID NHU	
(Use as many sheets as necessary)		Attorney Docket Number	AMAT/2592.C9/DSM/LOW K/JW	
Sheet 1	of 1	Submission Date	<u>_3/ &</u> , 2005	J

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
	C1	BAKLI, ET AL., "Materials and Processing for .025 µm Multilevel Interconnect," Microlelectronic Engineering 33 (1997) pp. 175-188.	
	C2	BHAN, ET AL., "Deposition of Stable Low K and High Deposition Rate SiF ₄ –Doped TEOS Fluorinated Silicon Dioxide (SiOF) Films," Thin Solid Films 308-309 (1997) pp. 507-511.	
	СЗ	C.F. LIN, ET AL., "Improved Ozone-Tetraethoxysilane Oxide Reliability for Deep Submicron Inter-Metal Dielectric Applications by Deposition of a Silane-Based Oxide Underlayer," Thin Solid Films 308-309 (1997) pp. 621-626.	
	C4	European Search Report from European Patent Office for 99906897.6 (2592.EP), dated 01/10/2005.	
	C5		
	C6		
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Examiner	Date Considered

This collection of information is required by 37 CFR 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450. If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. 1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.